**Electronic Supplementary Information (ESI)** 

## Epitaxial growth of orthorhombic NaTaO<sub>3</sub> crystals on SrTiO<sub>3</sub> (100) surface by flux coating

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## **Experimental**

NaTaO<sub>3</sub> crystals were grown on a single-crystalline SrTiO<sub>3</sub> (100) substrate in a twostep process: sputter deposition of a tantalum oxide (TaO<sub>x</sub>) thin film as a Ta source for NaTaO<sub>3</sub>, and its subsequent conversion into NaTaO<sub>3</sub>. First, a TaO<sub>x</sub> thin film was deposited on the SrTiO<sub>3</sub> (100) substrate (10 × 10 × 0.5 mm<sup>3</sup>, Shinkosha Co., Ltd.) by sputtering, using Ta (Furuya Metal Co., Ltd.) as a target and a simple magnetron sputtering system (JFC-1600, JEOL) under an Ar atmosphere. Next, a 2 M NaNO<sub>3</sub> solution was prepared using reagent-grade NaNO<sub>3</sub> powder (99.0%, Wako Pure Chemical Industries, Ltd.); 10  $\mu$ L of this solution was placed on the TaO<sub>x</sub>/SrTiO<sub>3</sub>, which had been dry-cleaned and hydrophilized by irradiation under vacuum-ultraviolet light ( $\lambda = 172$  nm) from a xenon excimer lamp (UER172-200, Ushio Inc.). The solution-coated TaO<sub>x</sub>/SrTiO<sub>3</sub> was dried in an electric oven at 100 °C for 30 min. The substrates were placed in a Pt case and covered with an alumina plate. The Pt case was heated to 600 °C at a rate of 100 °C·min<sup>-1</sup> in an infrared heating furnace and then naturally cooled to room temperature in the furnace without holding the temperature. The products were immersed in warm water to remove any residual NaNO<sub>3</sub>.

The TaO<sub>x</sub>/SrTiO<sub>3</sub> and NaTaO<sub>3</sub>/SrTiO<sub>3</sub> samples were examined by field-emission scanning electron microscopy (FESEM; SU8000, Hitachi) and transmission electron microscopy (TEM; EM-002B, Topcon and JEM-2010, JEOL). The elemental composition was investigated using an X-ray photoelectron spectrometer (XPS; JPS-9010MX, JEOL), energy-dispersive X-ray spectrometer (EDS; attached to a transmission electron microscope/scanning transmission electron microscope (TEM/STEM; JEM-2800, JEOL)), and X-ray diffractometer (XRD; SmartLab and MiniflexII, Rigaku) with Cu-K $\alpha$  radiation ( $\lambda$  = 0.154 nm). The samples for cross-sectional observations were prepared using a focused ion beam (FIB) system (JIB-4000, JEOL).



Figure S1. (a) Low- and (b) high-magnification cross-sectional TEM images of  $TaO_x/SrTiO_3$ .



Figure S2. (a) Digital photograph of TaO<sub>x</sub>/SrTiO<sub>3</sub>.



Figure S3. XPS spectra of  $TaO_x$  thin film deposited on an Al<sub>2</sub>O<sub>3</sub> substrate. The  $TaO_x$  thin film was also deposited on a sapphire substrate at the same time with a SrTiO<sub>3</sub> substrate.



Figure S4. (a) XRD pattern obtained from  $2\theta/\theta$  scan of NaTaO<sub>3</sub>/SrTiO<sub>3</sub>. (b) XRD pattern obtained from  $2\theta$  scan ( $\omega = 1.0^{\circ}$ ) of the SrTiO<sub>3</sub> substrate. XRD patterns of (c) NaTaO<sub>3</sub> (ICDD PDF data) and (d) SrTiO<sub>3</sub> (ICDD PDF data).



Figure S5. Illustrations of the growth mechanism of NaTaO<sub>3</sub> crystals from NaNO<sub>3</sub> and TaO<sub>x</sub>/SrTiO<sub>3</sub>. This figure shows the growth mechanism of epitaxially grown NaTaO<sub>3</sub> crystals rather than non-oriented ones.



Figure S6. Cross-sectional TEM image of a disordered NaTaO<sub>3</sub> crystal grown on SrTiO<sub>3</sub> substrate. Au particles were deposited on NaTaO<sub>3</sub>/SrTiO<sub>3</sub> before TEM observation in order to prevent the charging.



Figure S7. (a) Bright-field TEM image and (b–d) the corresponding SAED patterns of NaTaO<sub>3</sub>/SrTiO<sub>3</sub>. The incident electron beam was parallel to the [010] direction of SrTiO<sub>3</sub>.



Figure S8. Schematic illustration of NaTaO<sub>3</sub> crystal bounded by  $\{010\}$ ,  $\{10-1\}$ ,  $\{001\}$ , and  $\{100\}$  faces.



Figure S9. Schematic crystal structures of orthorhombic NaTaO3 and cubic SrTiO3.



Figure S10. Schematic crystal structures of orthorhombic NaTaO<sub>3</sub> (10-1) face and cubic SrTiO<sub>3</sub> (100) face.